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Application Number	09/691004
Filing Date	October 18, 2000
First Named Inventor	Forbes, Leonard
Group Art Unit	2826
Examiner Name	Unknown
Attorney Docket No: (00303.324US4

Sheet 1 of 1	1
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US PATENT DOCUMENTS						
Examiner Initial *	USP Document Number	Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	Filing Date If Appropriate
110	US-4113515	09/12/1978	Kooi, E., et al	148	1.5	03/29/1976
CAR.	US-4473836	09/25/1984	Chamberlain, S. G.	357	30	05/03/1982
Vegen .	US-5698869	12/16/1997	Yoshimi, M., et al	257	192	09/13/1995
Man	US-5858811	01/12/1999	Tohyama, S.	438	75	01/15/1997
Man	US-5886376	03/23/1999	Acovic, A., et al	257	316	07/01/1996
Jeffen	US-5976926	11/02/1999	Wu, J. Z., et al	438	237	10/10/1997
The	US-6031263	02/01/2000	Forbes L., et al	257	315	07/29/1997
Me	US-6084248	07/04/2000	Inoue, S.	257	66	02/03/1998
1992	US-6093937	07/25/2000	Yamazaki, S., et al	257	59	02/19/1997
Jeffen	US-6099574	08/08/2000	Fukuda, S., et al	703	14	12/16/1997
122-	US-6130147	10/10/2000	Major, J.S., et al	438	604	03/18/1997
Sel-	US-6144581	11/07/2000	Diorio, C. J., et al	365	185.03	11/30/1998
Alle.	US-6163066	12/19/2000	Forbes, L., et al	257	632	08/24/1998
yggen	US-6166401	12/26/2000	Forbes, L.	257	77	08/20/1998
VII Zu	US-6271566	08/07/2001	Tsuchiaki, M.	257	347	11/16/1999

Examiner Foreign Document No Initials*		Publication Date	Name of Patentee or Applicant of cited Document	Class	Subclass	T ²
Initials*	EP-0681333	11/08/1995	Tischler, M. A., et al	H01L	29/788	
	JP-63-289960	11/28/1988	Ito, T.	H01L	29/64	
Je lu	JP-07-115191	05/02/1995	Karuyankumaaru, D.	H01L	29/78	
Jan Jan	EP-0291951	08/04/1993	Takashi, I.	H01L	29/64	
Ele	JP-63-219172	09/12/1988	Aoki, S., et al	H01L	29/78	
Mu.	JP-01-115162	05/08/1989	Hirao, T., et al	H01L	29/78	
Iffler.	JP-63-181473	07/26/1988	Ukai, Y.	H01L	29/78	
Miller.	JP-62-122275	06/03/1987	Yamamoto, H., et al	H01L	27/78	
Offin.	JP-04-056769	02/24/1992	Futaki, T., et I	C23C	16/32	

	OTHE	R DOCUMENTS NON PATENT LITERATURE DOCUMENTS	
Examiner Initials*	Cite No 1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
The		BURNS, S.G. ,et al. , <u>In: Principles of Electronic Circuits,</u> West Publishing Company, St. Paul, MN, (1987), 382-383	
A.		WOLF, "Semiconductor Memory Process Integration", Silicon Processing for the VLSI Era Vol. 2: Process Integration, Lattice Press, California, (1990), 623-626	

V. MONDT **EXAMINER**

DATE CONSIDERED

May 10 '02



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Form 1449*

Atty. Docket No.: 303.324US4

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Applicant: Leonard Forbes et al.

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U.S. PATENT DOCUMENTS

Filing Date **Ryaminer Class Subclass If Appropriate Initial Document Number Date Name

FOREIGN PATENT DOCUMENTS

Translation **Examiner Date Country Class Subclass Initial

OTHER DOCUMENTS

**Examiner Initial

(Including Author, Title, Date, Pertinent Pages, Etc.)

"Dramatic Reduction of Sidegating in MODFET's", IEEE Lin, B., et al., Transactions on Electron Devices, 35, Abstract No. VA-6, pg. 2451,

> "Tunneling in Nanoscale Silicon Particles Embedded in an Tsu, R., et al., a-SiO2 Matrix", Abstract, IEEE Device Research Conference, pp. 178-179, (1996)

Zirinsky, S., et al., "Electrical Resistivity of Amorphous Silicon Resistor Films", Extended Abstracts of the Spring Meeting of the Electrochemical Washington, DC, pp. 147-149, (1971)

Examiner Date Considered

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